

Lithography Equipment Market Forecasts to 2034 – Global Analysis By Equipment Type (Deep Ultraviolet (DUV) Lithography Equipment, Extreme Ultraviolet (EUV) Lithography Equipment, I-Line Lithography Equipment, KrF Lithography Equipment, ArF Dry Lithography Equipment, ArF Immersion Lithography Equipment, Nanoimprint Lithography Equipment, Maskless Lithography Equipment, and Electron Beam Lithography Equipment), Wavelength, Process Node, Wafer Size, Application, End User, and By Geography

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Abstracts

According to Statistics MRC, the Global Lithography Equipment Market is accounted for \$50.7 billion in 2026 and is expected to reach \$100.3 billion by 2034 growing at a CAGR of 8.9% during the forecast period. Lithography equipment is the foundational technology of semiconductor manufacturing, used to pattern circuit designs onto silicon wafers. This equipment includes advanced systems such as Deep Ultraviolet (DUV) and Extreme Ultraviolet (EUV) lithography tools, which are essential for producing chips at increasingly smaller nodes. The market serves a wide range of applications including logic devices, memory devices (DRAM, NAND Flash), MEMS devices, power devices, CMOS image sensors, advanced packaging, and photonic devices. The primary end users are Integrated Device Manufacturers (IDMs), foundries, and Outsourced Semiconductor Assembly and Test (OSAT) companies. The escalating demand for high-performance computing, artificial intelligence, and advanced consumer electronics is a primary catalyst for market expansion, alongside the continuous industry drive toward miniaturization and enhanced chip performance.

Market Dynamics:

Driver:

Relentless demand for advanced semiconductor nodes and high-performance chips

The insatiable global demand for more powerful and energy-efficient semiconductors is the principal driver of the lithography equipment market. The proliferation of AI, high-performance computing, 5G, and autonomous vehicles necessitates chips fabricated at increasingly smaller nodes, which can only be produced using advanced lithography systems like EUV and high-NA EUV. As the semiconductor industry pushes toward nodes below 3nm, the complexity and cost of lithography equipment increase, but so does its essential nature. This technological arms race compels foundries and IDMs to continuously invest in next-generation tools, ensuring robust demand for lithography equipment throughout the forecast period.

Restraint:

Prohibitive costs and extreme technological complexity

The astronomical cost of research, development, and manufacturing of advanced lithography systems presents a significant restraint. A single advanced lithography machine can cost hundreds of millions of dollars, representing a massive capital expenditure that only the largest semiconductor manufacturers can afford. This creates a high barrier to entry, consolidating the market among a few key players and limiting the adoption of the most advanced technologies to a select group of fabs. Furthermore, the extreme technological complexity of these systems leads to long production lead times and intricate supply chains, which can be vulnerable to disruptions, potentially constraining the market's growth velocity.

Opportunity:

Growing demand for advanced packaging and photonics applications

The increasing adoption of advanced semiconductor packaging techniques, such as 3D integration and chiplets, presents a significant growth opportunity for the lithography equipment market. Advanced packaging requires precise lithography for interconnects and redistribution layers, creating a new and rapidly expanding application segment.

Additionally, the emerging field of silicon photonics, which uses light for data transmission, demands specialized lithography for manufacturing photonic integrated circuits. As the industry moves beyond traditional scaling to heterogeneous integration, these non-traditional applications are set to drive substantial demand for lithography tools, diversifying the market and fueling its expansion.

Threat:

Geopolitical tensions and supply chain fragility

The lithography equipment market is highly susceptible to geopolitical tensions and export controls, which pose a significant threat to its stability and growth. As semiconductor manufacturing has become a matter of national security, major economies are implementing restrictions on the export of advanced lithography tools to certain regions. This not only restricts the addressable market for equipment manufacturers but also disrupts global supply chains. Such fragmentation can lead to the development of parallel, less efficient supply chains, increasing costs and slowing down the pace of technological advancement across the industry.

Covid-19 Impact:

The COVID-19 pandemic initially caused significant disruptions to the lithography equipment market through factory shutdowns and supply chain bottlenecks. However, the subsequent surge in demand for consumer electronics, cloud services, and remote work infrastructure, coupled with the global chip shortage, created an urgent need for expanded semiconductor manufacturing capacity. This led to a wave of investment in new fabs and equipment, accelerating the market's growth trajectory. The pandemic underscored the strategic importance of semiconductor manufacturing, prompting governments and corporations to invest heavily in domestic production capabilities, a trend that continues to benefit the lithography equipment market.

The Logic Devices segment is expected to be the largest during the forecast period

The Logic Devices segment is expected to account for the largest market share during the forecast period, driven by the relentless pursuit of advanced computational power for AI, data centers, and consumer electronics. Logic chips, such as CPUs, GPUs, and AI accelerators, are at the forefront of process node development, requiring the most advanced and expensive lithography equipment like EUV and high-NA EUV. The intense competition among leading foundries and IDMs to produce the smallest, fastest,

and most power-efficient logic chips ensures that this segment remains the primary consumer of cutting-edge lithography tools, securing its dominant position throughout the forecast period.

The Foundries segment is expected to have the highest CAGR during the forecast period

Over the forecast period, the Foundries segment is predicted to witness the highest growth rate, fueled by the fabless business model and the massive capital expenditure programs of major semiconductor manufacturers. Foundries are the primary drivers of advanced node development, investing billions annually in new production capacity to meet the demand from a wide range of customers. As the demand for specialized chips from fabless companies continues to soar, foundries are compelled to continuously expand and upgrade their lithography capabilities. This sustained and massive investment ensures that the foundry end-user segment outpaces others in growth.

Region with largest share:

During the forecast period, the Asia-Pacific region is expected to hold the largest market share, driven by the concentration of the world's leading semiconductor foundries and memory manufacturers in countries including Taiwan, South Korea, China, and Japan. The region is the epicenter of global semiconductor production, housing the most advanced fabrication facilities. This dominance is supported by massive government investments and a robust local supply chain for electronics manufacturing. As the region continues to lead in both the production and consumption of semiconductors, its market share is projected to remain unchallenged.

Region with highest CAGR:

Over the forecast period, the Asia-Pacific region is anticipated to exhibit the highest CAGR, propelled by ongoing capacity expansion and technological upgrades in its semiconductor manufacturing hubs. Countries are aggressively investing in domestic semiconductor production to reduce import dependency and secure supply chains, driving substantial demand for new lithography equipment. The region's existing manufacturing base is also constantly upgrading to advanced nodes, further fueling growth. With continuous government support and private investment, Asia-Pacific is set to experience the fastest rate of expansion in the global lithography equipment market.

Key players in the market

Some of the key players in Lithography Equipment Market include ASML Holding N.V., Canon Inc., Nikon Corporation, Veeco Instruments Inc., EV Group (EVG), S?SS MicroTec SE, NuFlare Technology, Inc., JEOL Ltd., KLA Corporation, Applied Materials, Inc., SCREEN Holdings Co., Ltd., Shanghai Micro Electronics Equipment (SMEE) Co., Ltd., Carl Zeiss SMT GmbH, Ushio Inc., Intel Corporation, and Taiwan Semiconductor Manufacturing Company.

Key Developments:

In July 2026, Carl Zeiss SMT began moving staff into the first completed building of its 25,000-square-meter facility expansion in Oberkochen, Germany, expanding manufacturing throughput for the optical columns, mirrors, and lenses supplied exclusively for ASML's Low-NA and High-NA EUV scanners.

In June 2026, EV Group demonstrated advances in high-density wafer-to-wafer hybrid bonding and digital maskless lithography in collaboration with imec at the 2026 IEEE Electronic Components and Technology Conference (ECTC).

In June 2026, Nikon Precision expanded its digital lithography lineup specifically engineered to handle fine-pitch redistribution layers and advanced packaging schemes for next-generation AI chiplet assemblies.

In January 2026, Canon announced the development of inkjet-based adaptive planarization (IAP), an ultra-precise wafer surface smoothing technology derived from its nanoimprint lithography expertise, targeting commercial deployment in advanced memory and logic fabrication by 2027.

Equipment Types Covered:

Deep Ultraviolet (DUV) Lithography Equipment

Extreme Ultraviolet (EUV) Lithography Equipment

I-Line Lithography Equipment

KrF Lithography Equipment

ArF Dry Lithography Equipment

ArF Immersion Lithography Equipment

Nanoimprint Lithography Equipment

Maskless Lithography Equipment

Electron Beam Lithography Equipment

Wavelengths Covered:

365 nm (I-Line)

248 nm (KrF)

193 nm (ArF)

13.5 nm (EUV)

Process Nodes Covered:

Above 28 nm

16 nm–28 nm

7 nm–14 nm

5 nm and Below

Wafer Sizes Covered:

150 mm

200 mm

300 mm

Other Wafer Sizes

Applications Covered:

Logic Devices

Memory Devices

MEMS Devices

Power Devices

CMOS Image Sensors

Advanced Packaging

Photonic Devices

End Users Covered:

Integrated Device Manufacturers (IDMs)

Foundries

Outsourced Semiconductor Assembly and Test (OSAT) Companies

Research Institutes and Universities

Regions Covered:

North America

United States

Canada

Mexico

Europe

United Kingdom

Germany

France

Italy

Spain

Netherlands

Belgium

Sweden

Switzerland

Poland

Rest of Europe

Asia Pacific

China

Japan

India

South Korea

Australia

Indonesia

Thailand

Malaysia

Singapore

Vietnam

Rest of Asia Pacific

South America

Brazil

Argentina

Colombia

Chile

Peru

Rest of South America

Rest of the World (RoW)

Middle East

Saudi Arabia

United Arab Emirates

Qatar

Israel

Rest of Middle East

Africa

South Africa

Egypt

Morocco

Rest of Africa

What our report offers:

Market share assessments for the regional and country-level segments

Strategic recommendations for the new entrants

Covers Market data for the years 2023, 2024, 2025, 2026, 2027, 2028, 2030, 2032 and 2034

Market Trends (Drivers, Constraints, Opportunities, Threats, Challenges, Investment Opportunities, and recommendations)

Strategic recommendations in key business segments based on the market estimations

Competitive landscaping mapping the key common trends

Company profiling with detailed strategies, financials, and recent developments

Supply chain trends mapping the latest technological advancements

Free Customization Offerings:

All the customers of this report will be entitled to receive one of the following free customization options:

Company Profiling

Comprehensive profiling of additional market players (up to 3)

SWOT Analysis of key players (up to 3)

Regional Segmentation

Market estimations, Forecasts and CAGR of any prominent country as per the client's interest (Note: Depends on feasibility check)

Competitive Benchmarking

Benchmarking of key players based on product portfolio, geographical presence, and strategic alliances

Contents

1 EXECUTIVE SUMMARY

- 1.1 Market Snapshot and Key Highlights
- 1.2 Growth Drivers, Challenges, and Opportunities
- 1.3 Competitive Landscape Overview
- 1.4 Strategic Insights and Recommendations

2 RESEARCH FRAMEWORK

- 2.1 Study Objectives and Scope
- 2.2 Stakeholder Analysis
- 2.3 Research Assumptions and Limitations
- 2.4 Research Methodology
 - 2.4.1 Data Collection (Primary and Secondary)
 - 2.4.2 Data Modeling and Estimation Techniques
 - 2.4.3 Data Validation and Triangulation
 - 2.4.4 Analytical and Forecasting Approach

3 MARKET DYNAMICS AND TREND ANALYSIS

- 3.1 Market Definition and Structure
- 3.2 Key Market Drivers
- 3.3 Market Restraints and Challenges
- 3.4 Growth Opportunities and Investment Hotspots
- 3.5 Industry Threats and Risk Assessment
- 3.6 Technology and Innovation Landscape
- 3.7 Emerging and High-Growth Markets
- 3.8 Regulatory and Policy Environment
- 3.9 Impact of COVID-19 and Recovery Outlook

4 COMPETITIVE AND STRATEGIC ASSESSMENT

- 4.1 Porter's Five Forces Analysis
 - 4.1.1 Supplier Bargaining Power
 - 4.1.2 Buyer Bargaining Power
 - 4.1.3 Threat of Substitutes
 - 4.1.4 Threat of New Entrants

- 4.1.5 Competitive Rivalry
- 4.2 Market Share Analysis of Key Players
- 4.3 Product Benchmarking and Performance Comparison

5 GLOBAL LITHOGRAPHY EQUIPMENT MARKET, BY EQUIPMENT TYPE

- 5.1 Deep Ultraviolet (DUV) Lithography Equipment
- 5.2 Extreme Ultraviolet (EUV) Lithography Equipment
- 5.3 I-Line Lithography Equipment
- 5.4 KrF Lithography Equipment
- 5.5 ArF Dry Lithography Equipment
- 5.6 ArF Immersion Lithography Equipment
- 5.7 Nanoimprint Lithography Equipment
- 5.8 Maskless Lithography Equipment
- 5.9 Electron Beam Lithography Equipment

6 GLOBAL LITHOGRAPHY EQUIPMENT MARKET, BY WAVELENGTH

- 6.1 365 nm (I-Line)
- 6.2 248 nm (KrF)
- 6.3 193 nm (ArF)
- 6.4 13.5 nm (EUV)

7 GLOBAL LITHOGRAPHY EQUIPMENT MARKET, BY PROCESS NODE

- 7.1 Above 28 nm
- 7.2 16 nm–28 nm
- 7.3 7 nm–14 nm
- 7.4 5 nm and Below

8 GLOBAL LITHOGRAPHY EQUIPMENT MARKET, BY WAFER SIZE

- 8.1 150 mm
- 8.2 200 mm
- 8.3 300 mm
- 8.4 Other Wafer Sizes

9 GLOBAL LITHOGRAPHY EQUIPMENT MARKET, BY APPLICATION

- 9.1 Logic Devices
- 9.2 Memory Devices
 - 9.2.1 DRAM
 - 9.2.2 NAND Flash
- 9.3 MEMS Devices
- 9.4 Power Devices
- 9.5 CMOS Image Sensors
- 9.6 Advanced Packaging
- 9.7 Photonic Devices

10 GLOBAL LITHOGRAPHY EQUIPMENT MARKET, BY END USER

- 10.1 Integrated Device Manufacturers (IDMs)
- 10.2 Foundries
- 10.3 Outsourced Semiconductor Assembly and Test (OSAT) Companies
- 10.4 Research Institutes and Universities

11 GLOBAL LITHOGRAPHY EQUIPMENT MARKET, BY GEOGRAPHY

- 11.1 North America
 - 11.1.1 United States
 - 11.1.2 Canada
 - 11.1.3 Mexico
- 11.2 Europe
 - 11.2.1 United Kingdom
 - 11.2.2 Germany
 - 11.2.3 France
 - 11.2.4 Italy
 - 11.2.5 Spain
 - 11.2.6 Netherlands
 - 11.2.7 Belgium
 - 11.2.8 Sweden
 - 11.2.9 Switzerland
 - 11.2.10 Poland
 - 11.2.11 Rest of Europe
- 11.3 Asia Pacific
 - 11.3.1 China
 - 11.3.2 Japan
 - 11.3.3 India

- 11.3.4 South Korea
- 11.3.5 Australia
- 11.3.6 Indonesia
- 11.3.7 Thailand
- 11.3.8 Malaysia
- 11.3.9 Singapore
- 11.3.10 Vietnam
- 11.3.11 Rest of Asia Pacific
- 11.4 South America
 - 11.4.1 Brazil
 - 11.4.2 Argentina
 - 11.4.3 Colombia
 - 11.4.4 Chile
 - 11.4.5 Peru
 - 11.4.6 Rest of South America
- 11.5 Rest of the World (RoW)
 - 11.5.1 Middle East
 - 11.5.1.1 Saudi Arabia
 - 11.5.1.2 United Arab Emirates
 - 11.5.1.3 Qatar
 - 11.5.1.4 Israel
 - 11.5.1.5 Rest of Middle East
 - 11.5.2 Africa
 - 11.5.2.1 South Africa
 - 11.5.2.2 Egypt
 - 11.5.2.3 Morocco
 - 11.5.2.4 Rest of Africa

12 STRATEGIC MARKET INTELLIGENCE

- 12.1 Industry Value Network and Supply Chain Assessment
- 12.2 White-Space and Opportunity Mapping
- 12.3 Product Evolution and Market Life Cycle Analysis
- 12.4 Channel, Distributor, and Go-to-Market Assessment

13 INDUSTRY DEVELOPMENTS AND STRATEGIC INITIATIVES

- 13.1 Mergers and Acquisitions
- 13.2 Partnerships, Alliances, and Joint Ventures

13.3 New Product Launches and Certifications

13.4 Capacity Expansion and Investments

13.5 Other Strategic Initiatives

14 COMPANY PROFILES

14.1 ASML Holding N.V.

14.2 Canon Inc.

14.3 Nikon Corporation

14.4 Veeco Instruments Inc.

14.5 EV Group (EVG)

14.6 S?SS MicroTec SE

14.7 NuFlare Technology, Inc.

14.8 JEOL Ltd.

14.9 KLA Corporation

14.10 Applied Materials, Inc.

14.11 SCREEN Holdings Co., Ltd.

14.12 Shanghai Micro Electronics Equipment (SMEE) Co., Ltd.

14.13 Carl Zeiss SMT GmbH

14.14 Ushio Inc.

14.15 Intel Corporation

14.16 Taiwan Semiconductor Manufacturing Company

List Of Tables

LIST OF TABLES

Table 1 Global Lithography Equipment Market Outlook, By Region (2023–2034) (\$MN)

Table 2 Global Lithography Equipment Market Outlook, By Equipment Type (2023–2034) (\$MN)

Table 3 Global Lithography Equipment Market Outlook, By Deep Ultraviolet (DUV) Lithography Equipment (2023–2034) (\$MN)

Table 4 Global Lithography Equipment Market Outlook, By Extreme Ultraviolet (EUV) Lithography Equipment (2023–2034) (\$MN)

Table 5 Global Lithography Equipment Market Outlook, By I-Line Lithography Equipment (2023–2034) (\$MN)

Table 6 Global Lithography Equipment Market Outlook, By KrF Lithography Equipment (2023–2034) (\$MN)

Table 7 Global Lithography Equipment Market Outlook, By ArF Dry Lithography Equipment (2023–2034) (\$MN)

Table 8 Global Lithography Equipment Market Outlook, By ArF Immersion Lithography Equipment (2023–2034) (\$MN)

Table 9 Global Lithography Equipment Market Outlook, By Nanoimprint Lithography Equipment (2023–2034) (\$MN)

Table 10 Global Lithography Equipment Market Outlook, By Maskless Lithography Equipment (2023–2034) (\$MN)

Table 11 Global Lithography Equipment Market Outlook, By Electron Beam Lithography Equipment (2023–2034) (\$MN)

Table 12 Global Lithography Equipment Market Outlook, By Wavelength (2023–2034) (\$MN)

Table 13 Global Lithography Equipment Market Outlook, By 365 nm (I-Line) (2023–2034) (\$MN)

Table 14 Global Lithography Equipment Market Outlook, By 248 nm (KrF) (2023–2034) (\$MN)

Table 15 Global Lithography Equipment Market Outlook, By 193 nm (ArF) (2023–2034) (\$MN)

Table 16 Global Lithography Equipment Market Outlook, By 13.5 nm (EUV) (2023–2034) (\$MN)

Table 17 Global Lithography Equipment Market Outlook, By Process Node (2023–2034) (\$MN)

Table 18 Global Lithography Equipment Market Outlook, By Above 28 nm (2023–2034) (\$MN)

Table 19 Global Lithography Equipment Market Outlook, By 16 nm–28 nm (2023–2034) (\$MN)

Table 20 Global Lithography Equipment Market Outlook, By 7 nm–14 nm (2023–2034) (\$MN)

Table 21 Global Lithography Equipment Market Outlook, By 5 nm and Below (2023–2034) (\$MN)

Table 22 Global Lithography Equipment Market Outlook, By Wafer Size (2023–2034) (\$MN)

Table 23 Global Lithography Equipment Market Outlook, By 150 mm (2023–2034) (\$MN)

Table 24 Global Lithography Equipment Market Outlook, By 200 mm (2023–2034) (\$MN)

Table 25 Global Lithography Equipment Market Outlook, By 300 mm (2023–2034) (\$MN)

Table 26 Global Lithography Equipment Market Outlook, By Other Wafer Sizes (2023–2034) (\$MN)

Table 27 Global Lithography Equipment Market Outlook, By Application (2023–2034) (\$MN)

Table 28 Global Lithography Equipment Market Outlook, By Logic Devices (2023–2034) (\$MN)

Table 29 Global Lithography Equipment Market Outlook, By Memory Devices (2023–2034) (\$MN)

Table 30 Global Lithography Equipment Market Outlook, By DRAM (2023–2034) (\$MN)

Table 31 Global Lithography Equipment Market Outlook, By NAND Flash (2023–2034) (\$MN)

Table 32 Global Lithography Equipment Market Outlook, By MEMS Devices (2023–2034) (\$MN)

Table 33 Global Lithography Equipment Market Outlook, By Power Devices (2023–2034) (\$MN)

Table 34 Global Lithography Equipment Market Outlook, By CMOS Image Sensors (2023–2034) (\$MN)

Table 35 Global Lithography Equipment Market Outlook, By Advanced Packaging (2023–2034) (\$MN)

Table 36 Global Lithography Equipment Market Outlook, By Photonic Devices (2023–2034) (\$MN)

Table 37 Global Lithography Equipment Market Outlook, By End User (2023–2034) (\$MN)

Table 38 Global Lithography Equipment Market Outlook, By Integrated Device Manufacturers (IDMs) (2023–2034) (\$MN)

Table 39 Global Lithography Equipment Market Outlook, By Foundries (2023–2034) (\$MN)

Table 40 Global Lithography Equipment Market Outlook, By Outsourced Semiconductor Assembly and Test (OSAT) Companies (2023–2034) (\$MN)

Table 41 Global Lithography Equipment Market Outlook, By Research Institutes and Universities (2023–2034) (\$MN)

Note: Tables for North America, Europe, APAC, South America, and Rest of the World (RoW) Regions are also represented in the same manner as above.

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